33. (Amended) A scanning exposure method in which a pattern area of a mask is transferred onto a sensitive plate through a projection system in a scanning manner, the method comprising the steps of:

(a) irradiating the mask with a radiation in order to project an image portion of said pattern area of the mask onto the plate through said projection system;

(b) synchronously scanning each of the mask and the plate relative to said projection system in a scanning direction at a predetermined velocity ratio by using a scanning mechanism for the scanning exposure, wherein a scanning velocity of the mask is different from a scanning velocity of the plate;

(c) detecting a deviation between an ideal positional relation and an actual positional relation of the mask and the plate at a term of the scanning exposure; and

(d) correcting a position of the mask determined by said scanning mechanism for decreasing said detected deviation by using a fine moving mechanism provided on said scanning mechanism at the term of the scanning exposure.

36. (Amended) A scanning exposure method in which a pattern of a mask is transferred onto a sensitive plate through a projection system in a scanning manner, the method comprising the steps of:

(a) irradiating the mask with a radiation in order to project an image of said pattern of the mask onto the plate through said projection system;

(b) synchronously scanning each of the mask and the plate relative to said projection system by using a scanning mechanism for a scanning exposure wherein a scanning velocity of the mask is different from a scanning velocity of the plate;

(c) detecting a positional deviation between the mask and the plate at a term of the scanning exposure; and

(d) correcting a position of the mask determined by said scanning mechanism for decreasing said detected deviation at the term of the scanning exposure.

96. (Amended) A method for manufacturing a circuitry element with use of the method as defined in claim 68.

128. (Amended) A method for manufacturing a circuitry element with use of a scanning exposure apparatus made by using the method as defined in claim 97.

Please add the following claims:

--129. An apparatus according to claim 39, wherein during movement of said first object by said first driving system, said second driving system rotates said first object about a rotation axis passing through a predetermined point in an illumination region of exposure beam irradiated to said first object.--

--130. An apparatus according to claim 58, wherein said first measuring device includes a first interferometer system, and said second measuring device includes a second interferometer system.--

--131. An apparatus according to claim 130, wherein:

said first interferometer system has a measuring axis for measuring the position of said first object in said first direction, a measuring axis for measuring the position of said first object in a direction which crosses said first direction and a measuring axis for measuring information on rotation of said first object, and

said second interferometer system has a measuring axis for measuring the position of said second object in said second direction, a measuring axis for measuring the position of said second object in a direction which crosses said second direction and a measuring axis for measuring information on rotation of said second object.--

--132. An apparatus according to claim 37, further comprising:

a fourth driving system which moves said second object in a direction crossing said second direction.--

--133. An apparatus according to claim 70, wherein during movement of said first object by said first driving system, said second driving system rotates said first object about a rotation axis passing through a predetermined point in an illumination region of exposure beam irradiated to said first object.--

--~~134~~. A method according to claim ~~68~~, wherein said first driving system is capable of moving said first object by a longer distance than that moved by said second driving system.--

--135. A method according to claim 68, wherein during movement of said first object by said first driving system at least a portion of said second driving system moves in said first direction in order to move said first object.--

--~~136~~. A method according to claim ~~74~~, wherein said second driving system moves the first object based on the detected relative relationship.--

--137. A method according to claim 87, wherein said positional information of the first object includes positional information of said first object in a direction which crosses said first direction, and

said positional information of the second object includes positional information of said second object in a direction which crosses said second direction.--

--138. A method according to claim 87, wherein said positional information of the first object includes information on rotation of the first object; and

said positional information of the second object includes information on rotation of the second object.--

--139. A method according to claim 99, wherein during movement of said first object by said first driving system, said second driving system rotates said first object about a rotation axis passing through a predetermined point in an illumination region of exposure beam irradiated onto said first object.--

--140. A method according to claim 97, further comprising:

providing a fourth driving system which moves said second object in a direction which crosses said second direction.--